

2020년 2월 12일(수) ~ 14일(금) | 강원도 하이원리조트

2020년 2월 14일(금), 09:00~10:30 Room K (다이아몬드 I, 6층)

D. Thin Film Process Technology 분과 [FK1-D] Ferroelectric Materials

FK1-D-1 09:00~09:15	A Study on the Ferroelectric Phase Formation in Doped Hafnia Thin Films based on Classical Nucleation Theory Min Hyuk Park ¹ , Young Hwan Lee ² , and Cheol Seong Hwang ² ¹ School of Materials Science and Engineering, Pusan National University, ² Department of Materials Science and Engineering and Inter-University Semiconductor Research Center, College of Engineering, Seoul National University
FK1-D-2 09:15~09:30	Numerical Comparisons in Switching Kinetics of Hf _{0.5} Zr _{0.5} O ₂ Thin Films between the KAI and NLS Model Analyses Tae-Hyun Ryu, Dae-Hong Min, and Sung-Min Yoon Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University
FK1-D-3 09:30~09:45	Effects of High-pressure Hydrogen Annealing on the Ferroelectric Properties of W/Al:HfO ₂ /W Stacks Seungyeol Oh, In Keong Yoo, and Hyunsang Hwang Department of Materials Science and Engineering, POSTECH
FK1-D-4 09:45~10:00	Oxygen Partial Pressure Control during Sputtering Process on Ferroelectric Properties of Hf _{0.5} Zr _{0.5} O ₂ and Device Operations of Memory Transistors Dae-Hong Min ¹ , Tae-Hyun Ryu ¹ , Seung Eon Moon ² , and Sung-Min Yoon ¹ **Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University, ² ETRI
FK1-D-5 10:00~10:15	A Comparative Study on the Ferroelectric Performances in Atomic Layer Deposited Hf _{0.5} Zr _{0.5} O ₂ Thin Films Using Tetrakis(ethylmethylamino) and Tetrakis(dimethylamino) Precursors Seung Dam Hyun ¹ , Baek Su Kim ¹ , Min Hyuk Park ² , and Cheol Seong Hwang ¹ ¹ Department of Materials Science and Engineering and Inter-University Semiconductor Research Center, Seoul National University, ² School of Materials Science and Engineering, Pusan National University
FK1-D-6 10:15~10:30	Synaptic Plasticity Modulation of Ferroelectric Field-Effect Synapse Transistor Using Al-doped HfO ₂ Thin Film for Neuromorphic Applications So-Jung Yoon ¹ , Dae-Hong Min ¹ , Seung Eon Moon ² , and Sung-Min Yoon ¹ *Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University, ² ETRI